

VLSI Devices

Lecture 24


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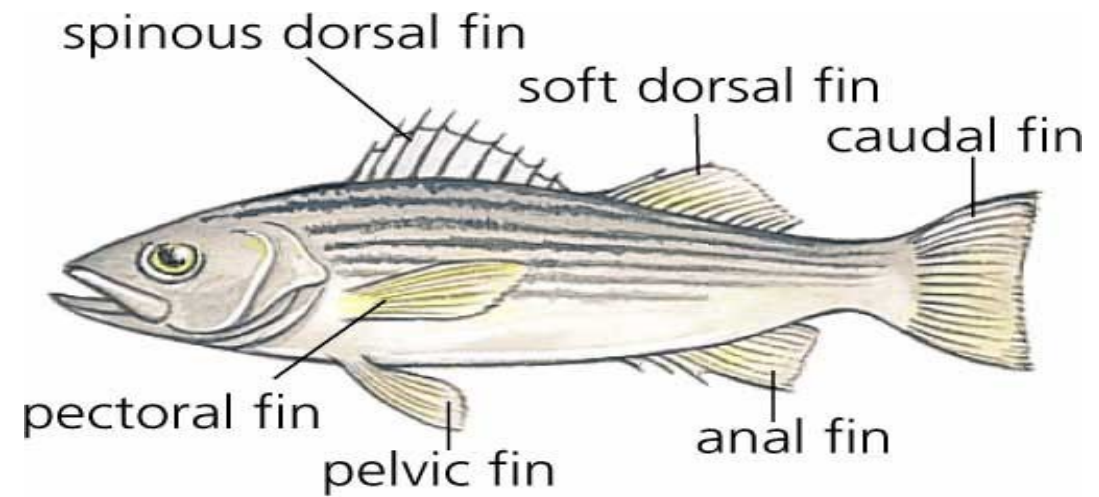
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Coverage

- Two YouTube lectures reserved for advanced topics
 - L14: ~~Substrate bias, channel mobility~~
 - L15: ~~3.2.1~~
 - L16: ~~3.2.1 (Continued)~~
 - L17: ~~Velocity saturation (3.2.2)~~
 - L18: ~~Channel length modulation and so on (3.2.3, 3.2.4, 3.2.5)~~
 - L19: ~~MOSFET scaling~~
 - L20: ~~MOSFET scaling (Continued)~~
 - L21: Quantum effect (4.2.4)
 - L22: Double-gate MOSFETs (10.3)
 - L23: FinFETs
 -  – L24: CFETs

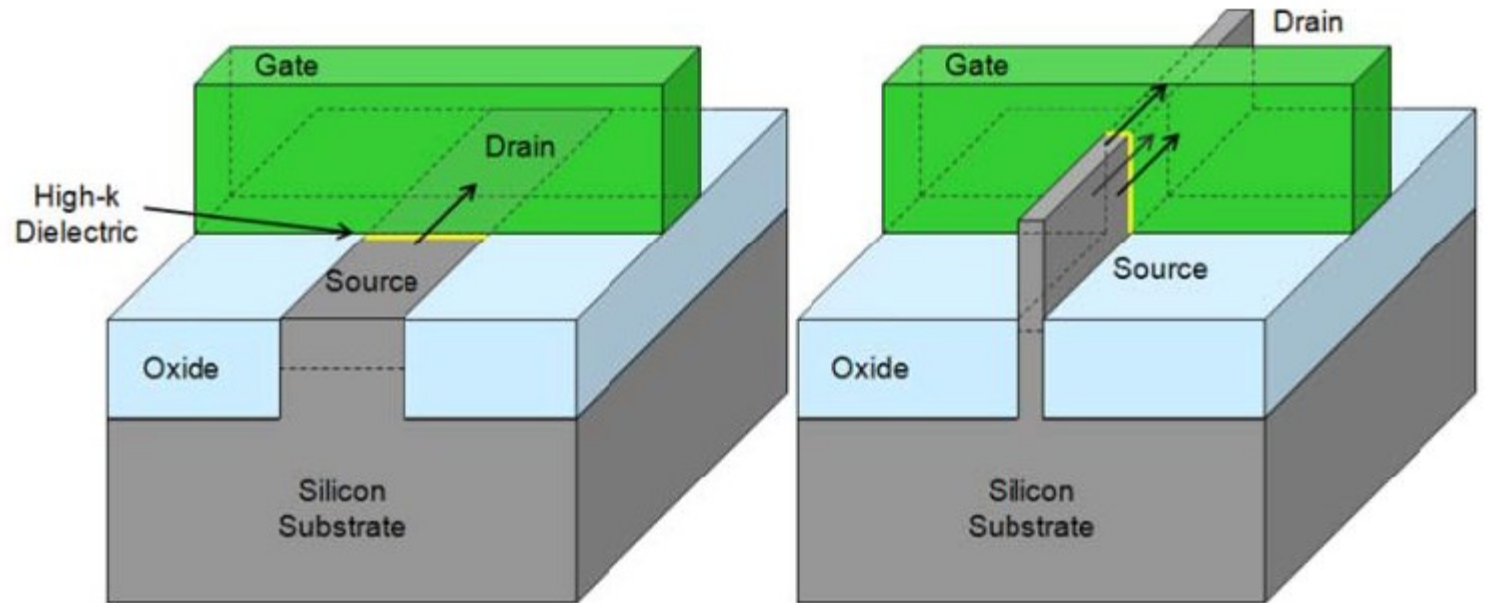
FinFET

- FinFET
 - Following its shape
 - Initially proposed as a SOI FinFET
 - Later, a bulk FinFET



Elizabeth Morales

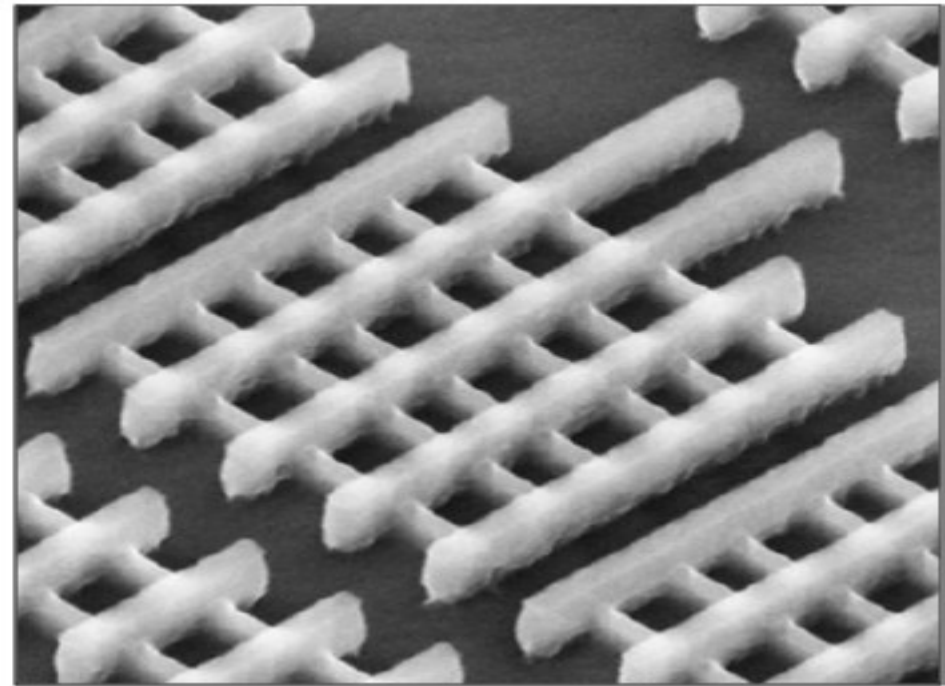
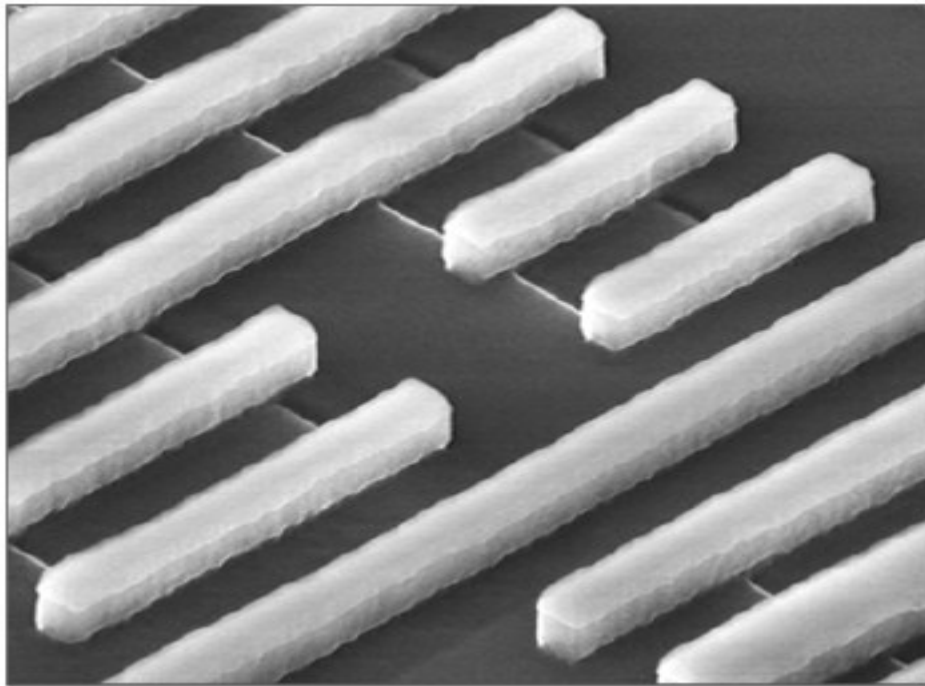
Fins (Google images)



Planar transistor structure (left) and FinFET structure (right)

SEM image

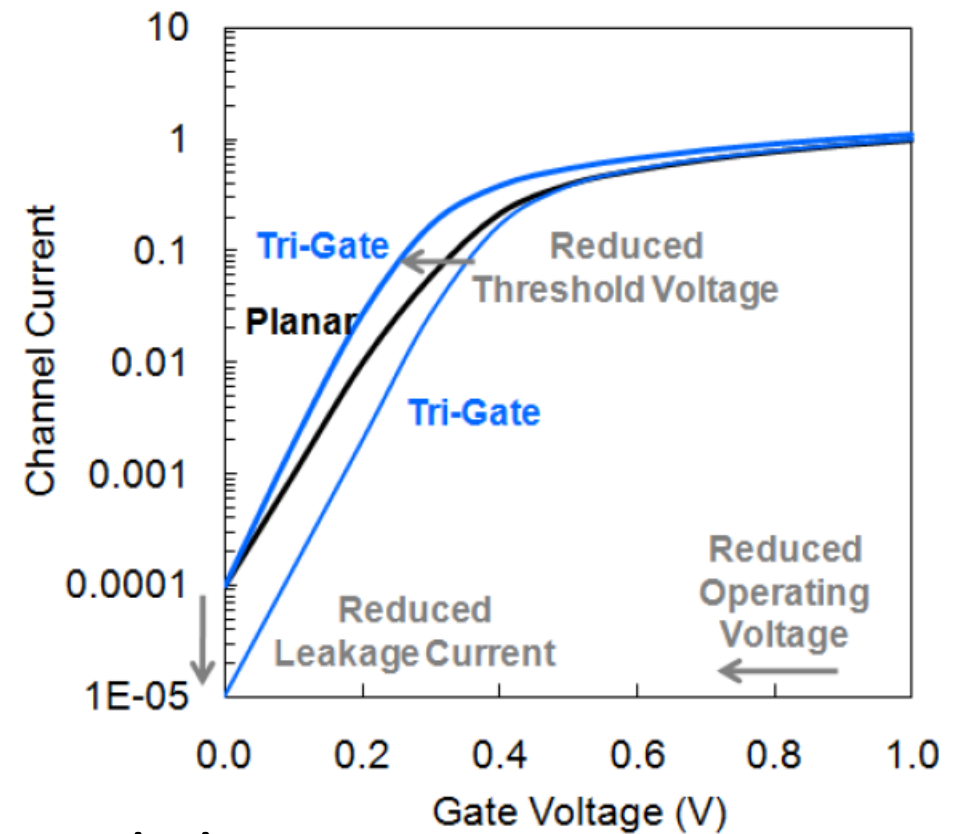
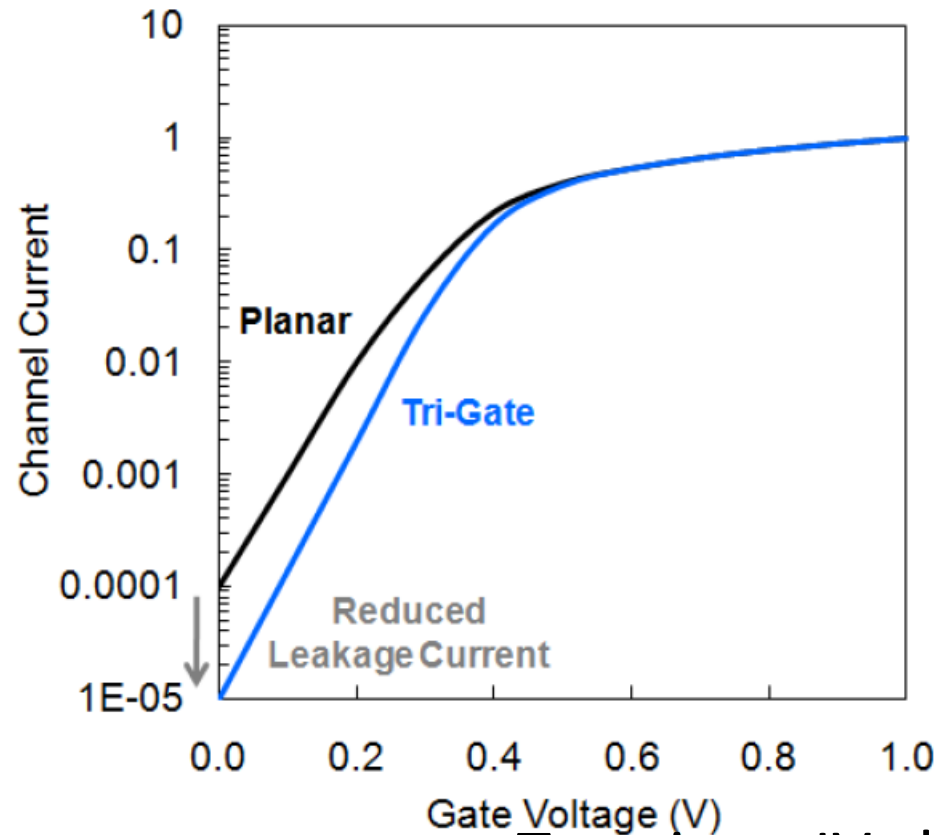
- FinFET
 - Improved electrostatic control of the channel region



32nm planar transistors (left) and 22nm FinFETs (right)

Performance

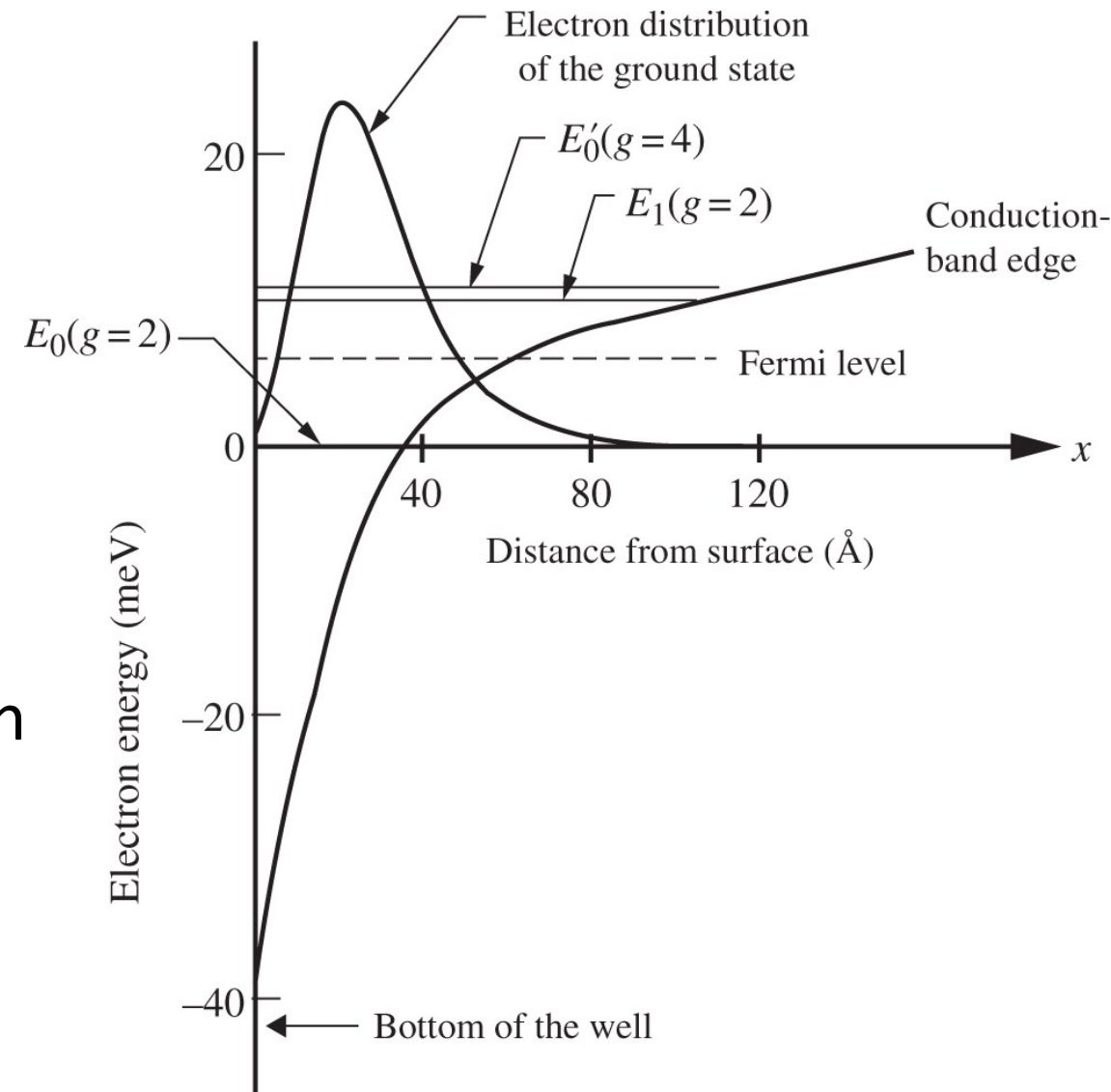
- Steeper sub-threshold slope
 - $\times 10$ off-state leakage reduction



Transistor IV characteristics

Quantum effect

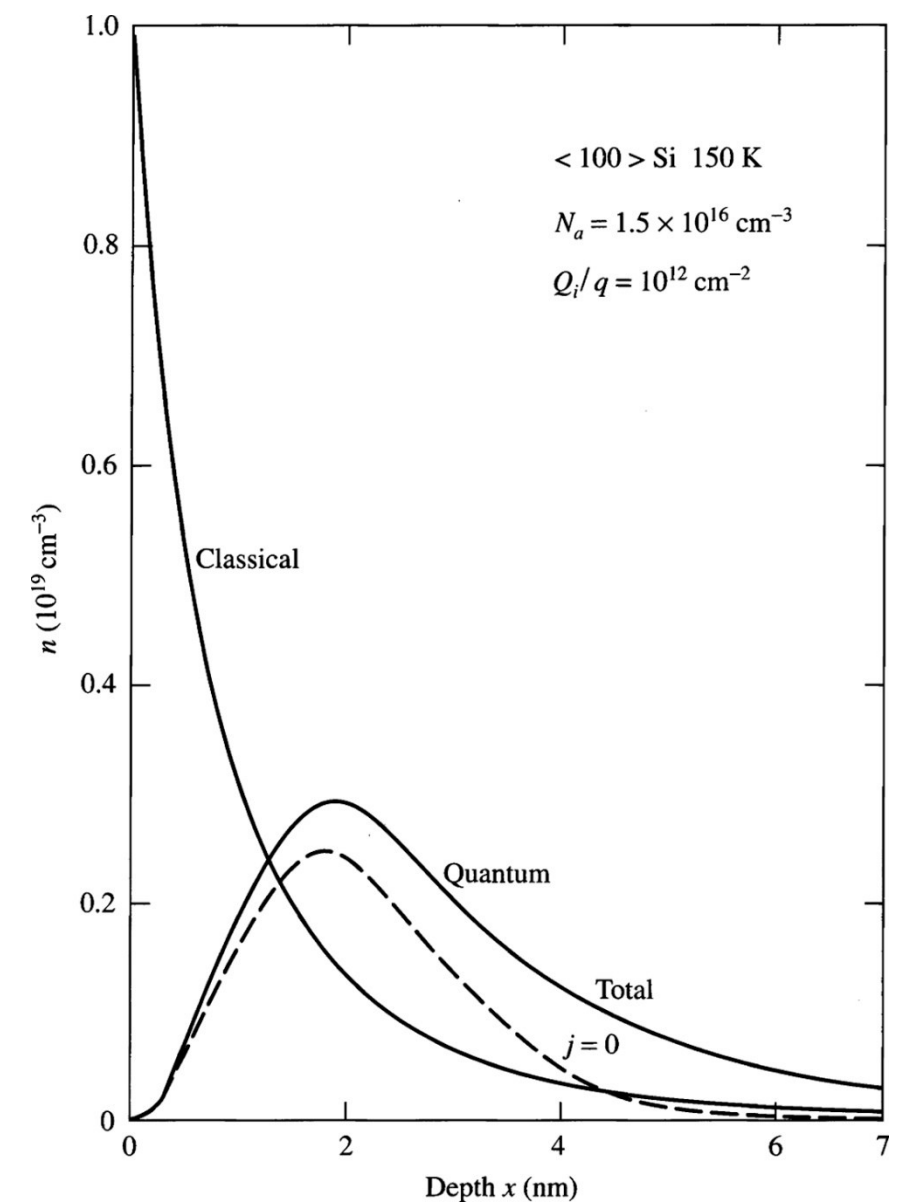
- Potential well formed by
 - The oxide barrier
 - The silicon conduction band
- Subbands
 - Quantized levels
 - Solutions of the Schrödinger equation
- Nearly zero n at the interface



Energy levels of inversion-layer electrons (Taur, Fig. 4.18)

Electron profile

- Classical vs. quantum-mechanical
 - Maximum n at the interface
- Quantum mechanical effects
 - At high fields, V_t becomes higher.
 - Effective gate oxide thickness is larger.



Classical and quantum-mechanical electron density (Taur, Fig. 4.19)

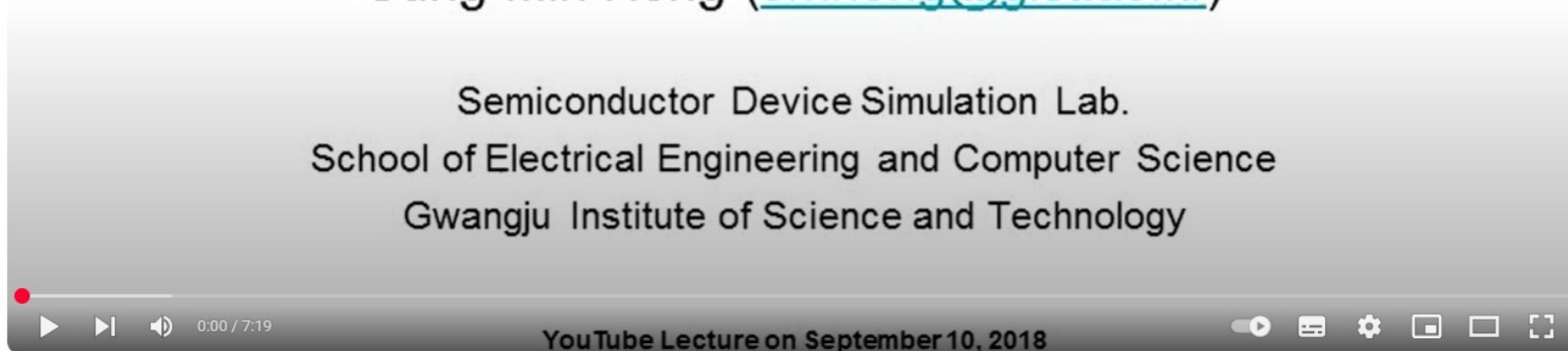
Poisson-Schrödinger solver

- General way to calculate the subband structure
 - It requires numerical analysis...
 - Interested? Watch my YouTube videos. (They are recorded in Korean.)

Schrödinger-Poisson solver – 1. Potential energy

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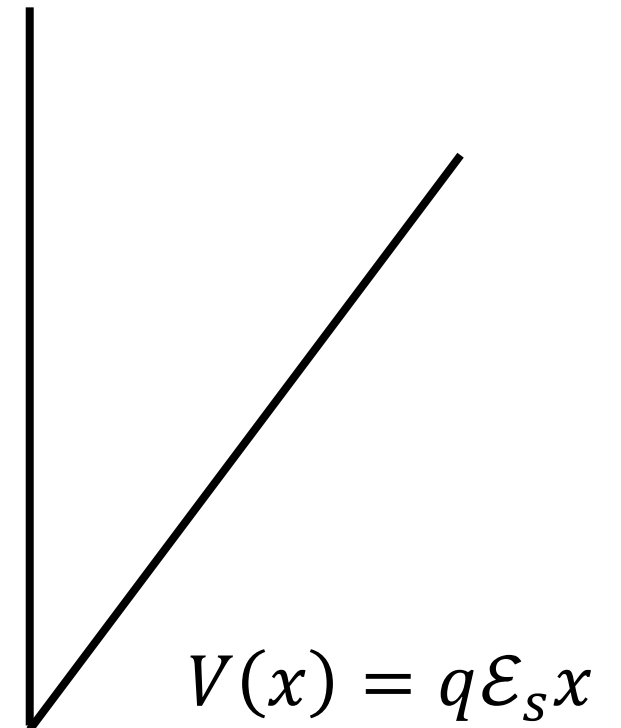


Triangular potential approximation

- Parabolic potential profile
 - However, it is further approximated as a linear potential. →
Triangular potential well

– Then, the Schrödinger equation reads

$$\left[-\frac{\hbar^2}{2m_{xx}} \frac{d^2}{dx^2} + q\mathcal{E}_s x \right] \psi(x) = E\psi(x)$$



Its solution

- Airy function

$$Ai(x) = \frac{1}{\pi} \int_0^{\infty} \cos\left(\frac{t^3}{3} + xt\right) dt$$

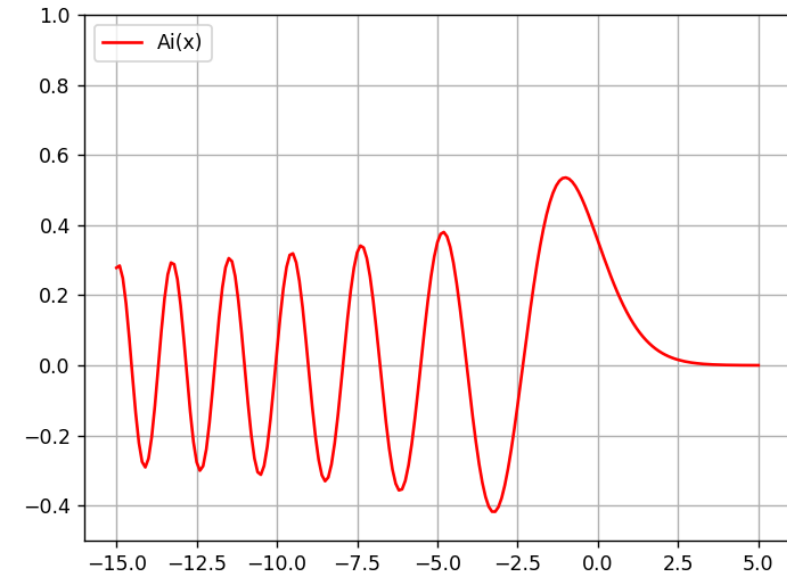
– Its second derivative is

$$\frac{d^2}{dx^2} Ai(x) = -\frac{1}{\pi} \int_0^{\infty} t^2 \cos\left(\frac{t^3}{3} + xt\right) dt$$

– Note that $\frac{d}{dt} \sin\left(\frac{t^3}{3} + xt\right) = (t^2 + x) \cos\left(\frac{t^3}{3} + xt\right)$.

– Therefore,

$$-xAi(x) + \frac{d^2}{dx^2} Ai(x) = -\frac{1}{\pi} \int_0^{\infty} \frac{d}{dt} \sin\left(\frac{t^3}{3} + xt\right) dt = 0$$



Simple manipulation

- The Schrödinger equation is written as

$$\left[\frac{d^2}{dx^2} - \frac{2m_{xx}}{\hbar^2} (q\mathcal{E}_s x - E) \right] \psi = \left[\frac{d^2}{dx^2} - \alpha^3 \left(x - \frac{1}{q\mathcal{E}_s} E \right) \right] \psi = 0$$

- With a new variable, $\xi = \alpha \left(x - \frac{1}{q\mathcal{E}_s} E \right)$, it becomes

$$\left[\frac{d^2}{d\xi^2} - \xi \right] \psi = 0$$

- The solution is $\psi(x) \sim Ai(\xi) = Ai \left(\alpha \left(x - \frac{1}{q\mathcal{E}_s} E \right) \right)$.

- At $x = 0$, the wavefunction must vanish:

$$-\alpha \frac{1}{q\mathcal{E}_s} E_j = a_j$$

Zeros of the Airy function

$$a_0 \approx -2.3381$$

$$a_1 \approx -4.0879$$

Eigenenergy

- Zeros are well approximated as $a_j \approx - \left[\frac{3\pi}{2} \left(j + \frac{3}{4} \right) \right]^{2/3}$.

– Then, the eigenenergy becomes

$$E_j = \frac{q\mathcal{E}_s}{\alpha} \left[\frac{3\pi}{2} \left(j + \frac{3}{4} \right) \right]^{2/3} = \left[\frac{3\hbar q\mathcal{E}_s}{4\sqrt{2m_{xx}}} \left(j + \frac{3}{4} \right) \right]^{2/3} \quad \text{Taur, Eq. (4.46)}$$

- There are two different m_{xx} values: $0.91m_0$ (degeneracy of 2, $g=2$) and $0.19m_0$ (degeneracy of 4, $g'=4$)

Total inversion charge per unit area

- For a subband,

- The number of electrons per unit area

$$n = \frac{4\pi k_B T}{h^2} g \sqrt{m_y m_z} \ln \left[1 + \exp \frac{E_f - E_{min}}{k_B T} \right]$$

Taur, Eq. (A12.5)

- Summation over subbands

$$Q_i^{QM} = -\frac{4\pi q k_B T}{h^2} \left(g m_t \sum_j \ln \left(1 + \exp \frac{E_f - E'_c - E_j}{k_B T} \right) + g' \sqrt{m_l m_t} \sum_j \ln \left(1 + \exp \frac{E_f - E'_c - E_{j'}}{k_B T} \right) \right)$$

Bottom of the conduction energy at the interface, $E'_c = E_c(\infty) - q\phi_s$

Taur, Eq. (4.49)

Subthreshold region

- In this case,

- It is well approximated as

$$Q_i^{QM} \approx -\frac{4\pi q k_B T}{h^2} \left(g m_t \sum_j \exp \frac{-E_j}{k_B T} + g' \sqrt{m_l m_t} \sum_j \exp \frac{-E_{j'}}{k_B T} \right) \exp \frac{E_f - E'_c}{k_B T}$$

- Using $E'_c = E_c(\infty) - q\phi_s$,

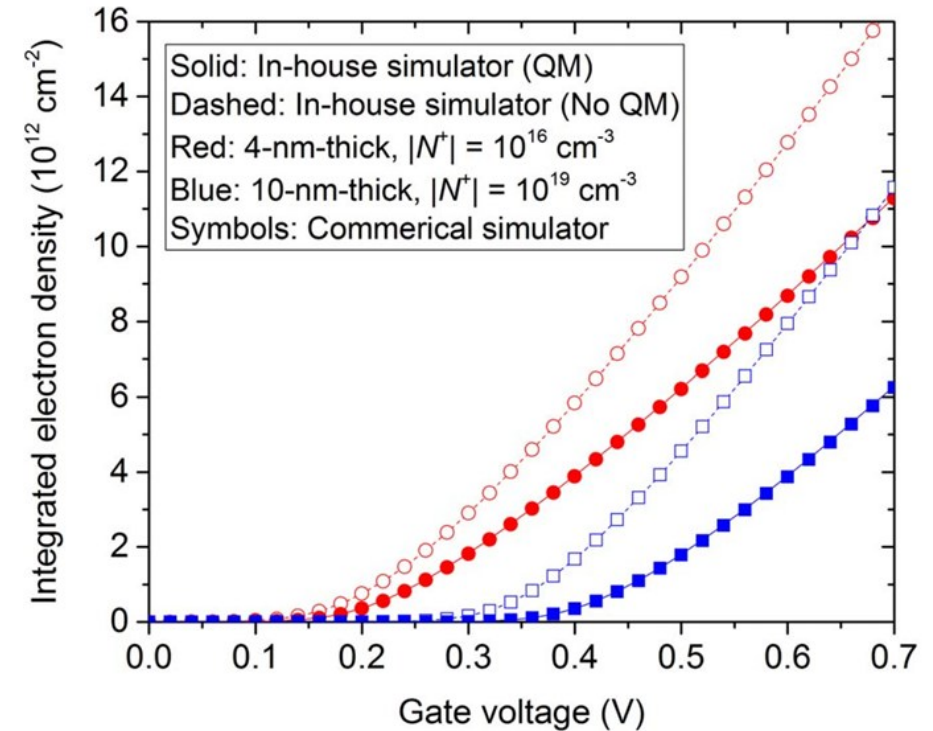
$$Q_i^{QM} \approx -\frac{4\pi q k_B T n_i^2}{h^2 N_c N_a} \left(g m_t \sum_j \exp \frac{-E_j}{k_B T} + g' \sqrt{m_l m_t} \sum_j \exp \frac{-E_{j'}}{k_B T} \right) \exp \frac{q\phi_s}{k_B T}$$

- (Note that $\exp \frac{E_f - E_c(\infty)}{k_B T} = \frac{n_i^2}{N_c N_a}$.)

Taur, Eq. (4.50)

Shift of threshold voltage

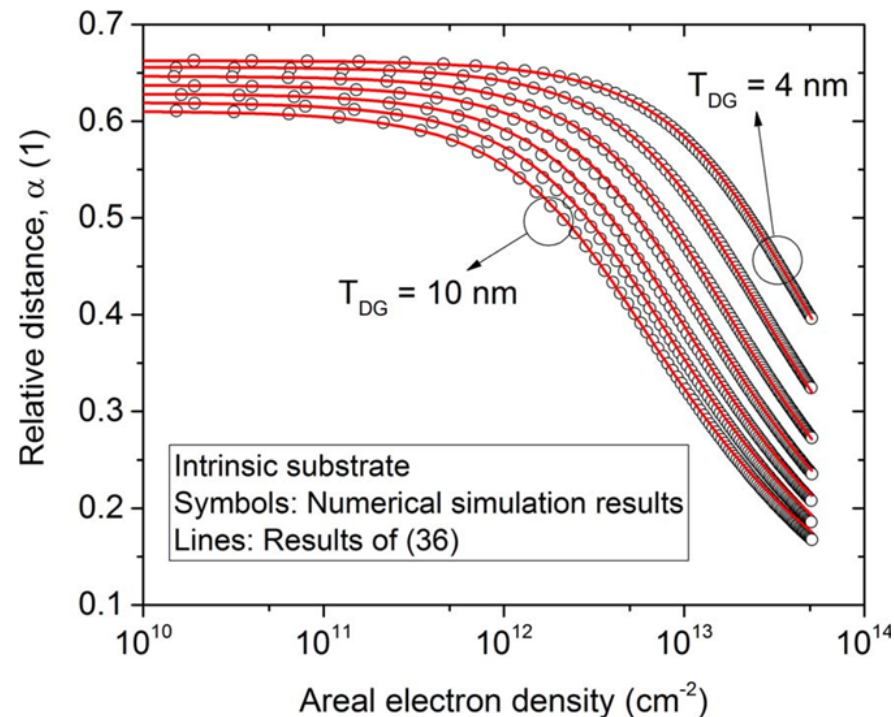
- Q_i^{QM} is smaller than its classical counterpart.
 - Additional band bending is required to achieve the same inversion charge per unit area
 - Example taken from our textbook:
 - When N_a is $3 \times 10^{18} \text{ cm}^{-3}$, $\Delta\phi_s^{QM}$ (additional surface potential to match the classical density) is 0.13 V.



Q-V relations for double-gate MOS structures

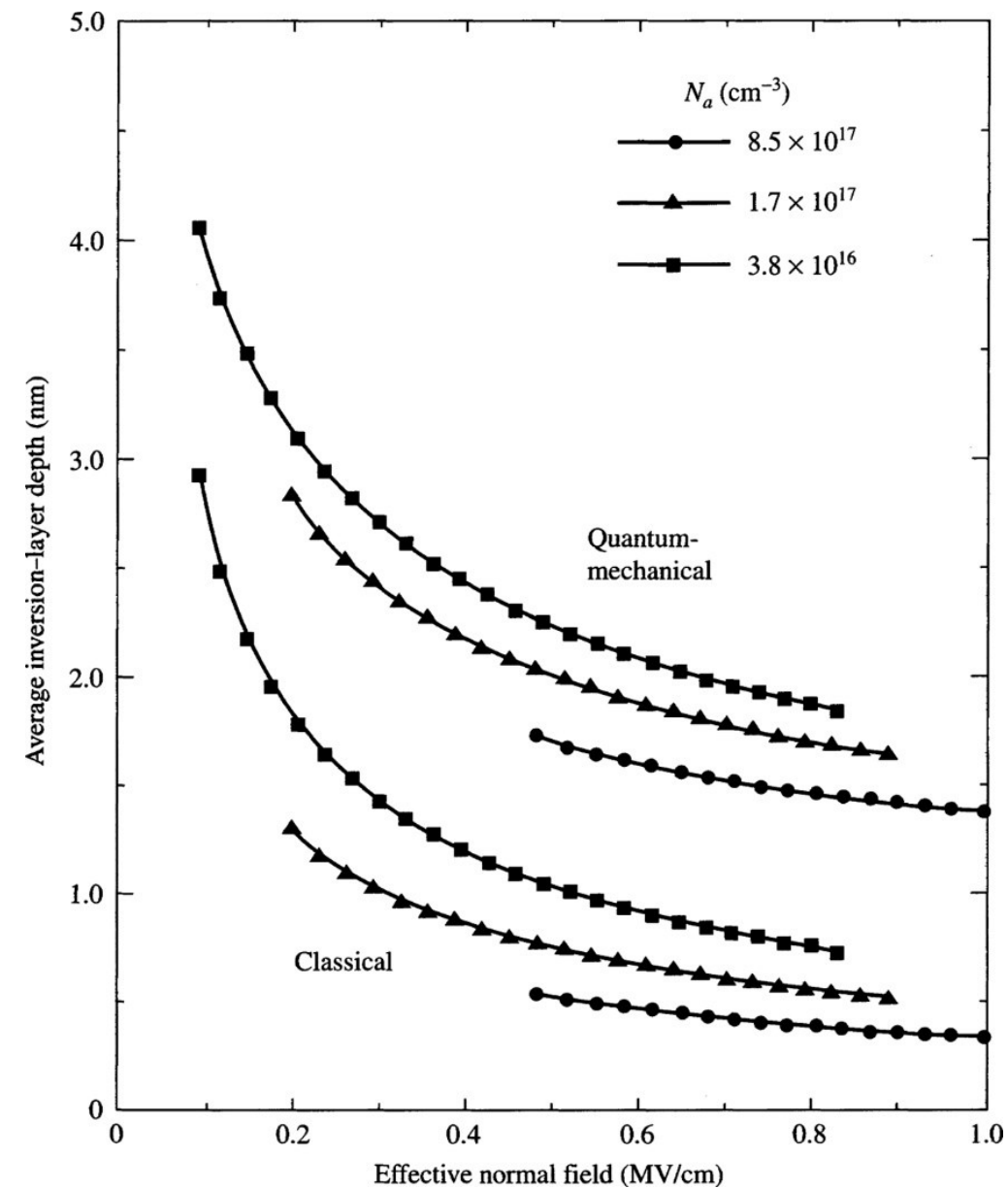
Inversion-layer depth

- Average distance
 - It reduces at a high gate voltage.
 - However, QM value is larger than CL one.



Average distance for double-gate MOS structures

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Inversion-layer depth
(Taur, Fig. 4.21)

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Thank you!